Subsystem			Specification	Current Results	Date Measured	Comments
Imaging						
	CD uniformity				N/A	*No lens qual measured prior to shutdown*
Illumination and Dose control						
	Slit uniformity	Setting 1	NA=0.85			*Annular, Si=0.69,So=0.93*
		Intensity	>1000mW	1023.22	2012-09-09	LUSU.99
		Slit Uniformity	<0.35%	0.25	2012-09-09	
		Scan Uniformity	<0.2%			
		Setting 2	NA=0.70			*Annular, Si=0.45, So=0.75*
		Intensity	>1130mW	N/A		
		setting 3	NA=0.85			Annular, Si=0.58,So=0.88
		Intensity	>1130mW	N/A		
	Dose System Performance	Setting1	<1.4%	1.343	2012-09-09	ODDP.99
	Dose Repeatability and Accuracy	Setting 1				
		Repeatability	<0.4%	0.127	2011-12-27	ODAR.67
		Accuracy	<1.5%	0.377	2011-12-27	ODAR.67
	Pupil Verification	Setting 1				
		Ellipticity	<3.0%	2.25	2012-07-07	LUPI.99
		Sigma Variation	<0.012%	0.003	2012-07-07	LUPI.99
		Sigma Repro	<0.005	N/A		
Projection						
	Aberrations	RMS z5-Z37	<1.8nm	0.16	2012-09-09	EMZC.50
		RMS spherical	<1.0nm	0.23	2012-09-09	EMZC.50
		RMS coma	<1.0nm	0.03	2012-09-09	EMZC.50
		RMS astigmatism	<1.0nm	0	2012-09-09	EMZC.50
	Non-correctable distortion setting1	NCE	<8.0nm	N/A		
	Image plane deviation @ 70nm setting1	IPD	<55nm	207	2012-04-04	FPSQ.11 - Don't know if this data is reliable as it is only exposed on one chuck
	Astigmatism @ 70nm setting 1	Ast	<35	124	2012-04-04	FPSQ.11 - Don't know if this data is reliable as it is only exposed on one chuck
	Long Range Stray light setting 1	Max	<1.0	0.74	2012-09-09	EMCA.95
	Short Range Stray light setting 1	Max	<1.5	N/A		
Focus and Levelling						
	Wafer Map reproducibility	99.70%	<15nm	5.8	2006-08-20	EMWA.01
	Full wafer focus uniformity		<15nm			
	Chuck to Chuck Focus difference		<60nm	N/A		No data -- system ran dual chuck mode
	Focus stability		<40nm	N/A		Not measured prior to shut down.
Dynamic Performance						
	Moving standard deviation	mean +3sig	<7.0nm	5	2012-09-08	TSDA.16
	Moving average	mean +3sig	<3.0nm	0.8	2012-09-08	TSDA.16
	Reticle Masking Accuracy		<300um	N/A		
Overlay						
	Stage Repeatability		<4.0nm	0	XYWO.06	*9/3/2011 - repeatability value 0.0 not sure if accurate*
	Stage grid verification		<7.0nm	8.5	FGGO.02	*2007-02-26*
	Single Machine Overlay	overlay max 99.7%	<8.0nm	4.5,3.3nm	XYNO.23	*2005-01-16*
	Matched Machine Overlay	overlay max 99.7%	<14.0	3.5,2.9nm	XYMO.68	*2012-09-14*
Productivity						
	Throughput	wafer/hour	>150w/hr	N/A		no recent data

Subsystem			Specification	Current Results	Date Measured	Comments
	Reticle Exchange Time		<13s	N/A		no recent data
	Lot Overhead		<13s	N/A		no recent data
Reticle Masking Accuracy						
						no recent data